ACKNOWLEDGEMENT RECEIPT

Electronic Version 1.1 Stylesheet Version v1.1.1

Title of

EFS ID:

Method for forming silicon dioxide film using siloxane

Submision Type: Information Disclosure

Statement

Application Number:

10/782094

Confirmation

87192

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First Named Applicant:

Jae-eun Park SAM-0483

Attorney Docket Number:

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File Listing:

DOC. NAME	The Halle	Di20 (D)(03)	Produced (yyyymmdd
us-ids	SamsungFourEightyThreePartThree-usid st.xml		2005-06-28
us-ids	us-ids.dtd	7763	2005-06-28
us-ids	us-ids.xsl		2005-06-28
package-data	SamsungFourEightyThreePartThree-pkda .xml	2056	2005-06-28
package-data	package-data.dtd	27025	2005-06-28
package-data	us-package-data.xsl	19263	2005-06-28
	00070		

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